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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/464,297 12/1:		12/15/1999	15/1999 SHELDON ARONOWITZ	99-039	7342
24319	7590	08/08/2003			
LSI LOGI			EXAMINER VINH, LAN		
1621 BARI MS: D-106	LEGAL	_			
MILPITAS, CA 95035			ART UNIT	PAPER NUMBER	
				1765	
				DATE MAILED: 08/08/2003	

Please find below and/or attached an Office communication concerning this application or proceeding.

PTO-90C (Rev. 07-01)

4		Application No.	Applicant(s)			
Ř	Advisory Action	09/464,297	ARONOWITZ ET AL.			
i N	Advious Action	Examiner	Art Unit			
	•	Lan Vinh	1765			
	The MAILING DATE of this communication app	ars on the cov r sh et with th	correspondence address			
There inal r condi	REPLY FILED 28 July 2003 FAILS TO PLACE THE fore, further action by the applicant is required to a rejection under 37 CFR 1.113 may only be either: (1 tion for allowance; (2) a timely filed Notice of Appe ination (RCE) in compliance with 37 CFR 1.114.	void abandonment of this appliced in the control of	cation. A proper reply to a chiple can be a chiple cation.			
_	PERIOD FOR RE	PLY [check either a) or b)]				
a) [b) [<u> </u>	isory Action, or (2) the date set forth in than SIX MONTHS from the mailing date or	f the final rejection.			
nave be 37 CFF b) abo	tensions of time may be obtained under 37 CFR 1.136(a). The date of filed is the date for purposes of determining the period of extens at 1.17(a) is calculated from: (1) the expiration date of the shortened we, if checked. Any reply received by the Office later than three mo patent term adjustment. See 37 CFR 1.704(b).	sion and the corresponding amount of the statutory period for reply originally set in	fee. The appropriate extension fee under the final Office action; or (2) as set forth in			
	A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CFR	R 1.191(d)), to avoid dismissal				
2.🛛	The proposed amendment(s) will not be entered be	ecause:	•			
(a) $oxed{oxed}$ they raise new issues that would require furthe	er consideration and/or search (see NOTE below);			
) \square they raise the issue of new matter (see Note t	• •				
(с	 they are not deemed to place the application i issues for appeal; and/or 	n better form for appeal by mat	erially reducing or simplifying the			
(d) \square they present additional claims without cancel	ing a corresponding number of	finally rejected claims.			
	NOTE: <u>See Continuation Sheet</u> .	•				
3.□	Applicant's reply has overcome the following reject	5				
4.	Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a s	eparate, timely filed amendment			
5.	The a) affidavit, b) exhibit, or c) request for application in condition for allowance because:	r reconsideration has been cons	sidered but does NOT place the			
6.□	The affidavit or exhibit will NOT be considered becaused by the Examiner in the final rejection.	cause it is not directed SOLELY	to issues which were newly			
7.🖂	For purposes of Appeal, the proposed amendment(s) a) will not be entered or b) will be entered and an explanation of how the new or amended claims would be rejected is provided below or appended.					
	The status of the claim(s) is (or will be) as follows:					
	Claim(s) allowed: None.					
	Claim(s) objected to:		•			
	Claim(s) rejected: 4,7 and 9-24.		·			
	Claim(s) withdrawn from consideration:					
8.	The proposed drawing correction filed on is	a) approved or b) disapp	proved by the Examiner.			
9.	Note the attached Information Disclosure Statemen					
0.	Other:					
			NADINE G. NORTON PRIMARY EXAMINATE			
	•		Mad Not			

Continuation of 2. NOTE: The newly added limitations of "leaving a silicon oxide layer having a thinner region of uniform thickness", "leaving a silicon oxide layer of uniform thickness", as recited in amended claims 4, 11, "one or more unmasked regions of silicon oxide layer on", "unmasked region of said silicon oxide layer", as recited in amended claim 19, "forming, in an ... of uniform thickness" and "to remove a uniform thickness ... of said silicon oxide layer", as recited in amended claim 24, raise new issue that would require further consideration..